



제 29회 한국반도체학술대회

The 29th Korean Conference on Semiconductors

2022년 1월 24일(월)~ 26일(수) | 강원도 하이원 그랜드호텔(컨벤션타워)

2022년 1월 26일(수), 09:00-10:30

Room A (에메랄드 I, 5층)

D. Thin Film Process Technology 분과

[WA1-D] Thin Film Process II

좌장: 최병준 교수(서울과학기술대학교), 송봉근 교수(홍익대학교)

<p>WA1-D-1 09:00-09:15</p>	<p>HfO₂ Films Having Wide ALD Window Using a Novel Heteroleptic Hf Precursor by Plasma-Enhanced Atomic Layer Deposited Wan-Ho Choi¹, Hohoon Kim², Younghun Byun², and Jin-Seong Park¹ ¹Division of Materials Science and Engineering, Hanyang University, ²Mecaro Advanced Precursor System R&D center, MECARO Co., Ltd.</p>
<p>WA1-D-2 09:15-09:30</p>	<p>Enhanced Characteristics of HfO₂ Deposited by Atomic Layer Deposition Using Novel Precursor with Improved Thermal Stability Seung Won Lee, Min Ji Jeong, and Ji-Hoon Ahn Department of Materials Science and Chemical Engineering, Hanyang University</p>
<p>WA1-D-3 09:30-09:45</p>	<p>Improved PEALD ZrO₂ Film Properties Using Hollow Cathode Plasma Source Chang Ik Choi, Jae Chan Park, Seung Won Lee, Min Ji Jung, Ji Hoon Ahn, and Tae Joo Park Department of Materials Science and Chemical Engineering, Hanyang University</p>
<p>WA1-D-4 09:45-10:00</p>	<p>Improvement of Electrical Properties of ALD ZrO₂ Driven by Controlling Surface Reaction with Plasma Source Ae Rim Choi, Yeon Je Yoo, and Il Kwon Oh Department of Electrical and Computer Engineering, Ajou University</p>
<p>WA1-D-5 10:00-10:15</p>	<p>The Effect of Al₂O₃ Passivation Layer between ZrO₂/Ge Substrate Depending on Annealing Temperature Byoung Jun Won, Geun Ha Oh, and Il-Kwon Oh Department of Electrical and Computer Engineering, Ajou University</p>
<p>WA1-D-6 10:15-10:30</p>	<p>Substrate-dependent Selective Atomic Layer Etching of Metal Oxides Jeongbin Lee, Jaehong Noh, Tae Joo Park, and Woo-Hee Kim Department of Materials Science and Chemical Engineering, Hanyang University</p>